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## APPLICATION FOR LETTERS PATENT OF THE UNITED STATES

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BY: Carrie Parker  
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### SPECIFICATION

To all whom it may concern:

Be It Known, That We, **Jeff Brown, a citizen of the United States of America, 3624 Goodell Lane, Fort Collins, Colorado 80526 and Chang Jung, a citizen of the Republic of Korea, 3023 Indigo Circle South, Fort Collins, Colorado 80528**, have invented certain new and useful improvements in "**METAL PROGRAMMABLE SELF-TIMED MEMORIES**", of which We declare the following to be a full, clear and exact description:

## BACKGROUND OF THE INVENTION

### 1. Technical Field:

The present invention is directed generally toward a method and apparatus for  
5 implementing a self-timed static random-access memory in an integrated circuit.

### 2. Description of the Related Art:

There are two basic types of semiconductor random-access memory (RAM) circuits in  
common use. Static random-access memory (SRAM) stores data by way of a feedback circuit.  
10 Dynamic random-access memory (DRAM) stores data as electrostatic charge on a capacitor. In  
general, RAM circuits are configured in two-dimensional arrays of individual memory cells, with  
each memory cell storing one bit. A word of data may be accessed from one or more memory  
circuits by addressing the cells that store the data by row and column addresses and reading or  
writing data to or from the addressed cells. In a typical SRAM array, each memory word is  
15 stored in a separate row and addressed by asserting a "word line," while the individual bits of  
each word are read from and written to the memory array using "bit lines." In a typical single-  
port memory array, all bit lines for a particular bit position are connected together. For example,  
all memory cells representing bit position 4 of a word typically share common bit lines, but have  
separate word lines. The generic term for word lines and bit lines is "address lines," as address  
20 lines are used for *addressing* individual memory cells.

Memory circuits may be single-port or multi-port memory circuits. Single-port circuits  
are capable of allowing access to a single memory location (i.e., one cell or a group of cells at a  
single memory address). Multi-port circuits allow two or more memory addresses to be accessed  
concurrently. Specifically, a "port" is a set of related address lines that together are sufficient to  
25 perform one memory access at a particular point in time. Thus, a single-port memory cell, which  
only has one port, is capable of supporting only one access at a time, while a dual-port memory  
cell, which has two ports, is capable of supporting two simultaneous memory accesses. Higher-  
order multi-port cells (e.g., three-port, four-port, etc...), which support larger numbers of  
simultaneous accesses, are also possible.

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**Figure 1** is a diagram of a typical six-transistor single-port complementary metal-oxide semiconductor (CMOS) SRAM circuit **100** as known in the art. SRAM circuit **100** is perhaps the most common circuit topology for a single-port SRAM. SRAM circuit **100** includes a flip-flop circuit, which is formed by cross-coupling two logic inverters formed by transistors **Q1-Q4**, and  
 5 two pass-gate transistors (also called access transistors) **Q5** and **Q6**.

Specifically, PMOS (p-channel MOS) transistor **Q3** and NMOS (n-channel MOS) transistor **Q1** form one CMOS inverter and PMOS transistor **Q4** and NMOS transistor **Q2** form another CMOS inverter. Referring to the inverter formed by transistors **Q3** and **Q1**, the gates of transistors **Q3** and **Q1** are connected together to form an input node **110** to the inverter. The  
 10 sources of transistors **Q3** and **Q1** are connected together to form an output node **112** of the inverter. The drain of transistor **Q3** is connected to positive supply rail **Vdd 106**, making transistor **Q3** the “pull-up” transistor of the inverter. The drain of transistor **Q1** is connected to negative (or “low”) supply rail **Vss 108**, making transistor **Q1** the “pull-down” transistor of the inverter. Transistors **Q4** and **Q2** are similarly configured as a CMOS inverter. In SRAM circuit  
 15 **100**, the CMOS inverter formed by transistors **Q4** and **Q2** is cross-coupled with the CMOS inverter formed by transistors **Q3** and **Q1**. Thus, node **110**, which is the input node of the inverter formed by transistors **Q3** and **Q1**, forms the output node of the inverter formed by transistors **Q4** and **Q2**, and node **112**, which is the output node of the inverter formed by transistors **Q3** and **Q1**, forms the input node of the inverter formed by transistors **Q4** and **Q2**.

20 Nodes **110** and **112** are referred to as the “internal nodes” of SRAM circuit **100**. For the purposes of this document, the term “internal node” is defined as a data-storing node in an SRAM circuit. In the case of circuit **100**, nodes **110** and **112**, because they form part of the feedback loop of the cross-connected CMOS inverters (transistors **Q1-Q4**), are data-storing nodes and are, therefore, “internal nodes,” for the purposes of this document.

25 Pass-gate transistors **Q5** and **Q6** are MOS transistors configured as switches. The gates of transistors **Q5** and **Q6** are connected to word line **102**. The source and drain of pass-gate transistor **Q5** are connected between bit line **104** and node **112**. The source and drain of pass-gate transistor **Q6** are connected between inverse bit line **106** and node **110**. Pass-gate transistors **Q5** and **Q6** are turned on when word line **102** is selected (i.e., raised in voltage) and connect bit

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lines **104** and **106** to the flip-flop formed by transistors **Q1-Q4**. When pass-gate transistors **Q5** and **Q6** switch bit lines **104** and **106** into connection with internal nodes **110** and **112**, the data stored by memory circuit **100** becomes available on bit line **104**, and the complement of that data becomes available on inverse bit line **106**, so reading from memory circuit **100** becomes possible.

5 To write data to memory circuit **100**, word line **102** is selected, the data to be stored is asserted on bit line **104**, and the complement of that data is asserted on inverse bit line **106**. Since transistors **Q1-Q4** form a bistable circuit (i.e., a circuit with two stable states), asserting the new data on bit lines **104** and **106** results in putting this bistable circuit into the stable state associated with the stored data. When word line **102** is no longer asserted, transistors **Q1-Q4** maintain the  
10 same stable state, and thus store the written data until power is no longer available from power supply rails **108** and **109**.

**Figure 2** is a diagram showing how a typical SRAM memory array **200** is configured from individual memory cells. Memory array **200** is a single-port memory array (i.e., it consists of only single-port memory cells and supports only one memory access at a time), although  
15 multi-port memory arrays are also common. In memory array **200**, words are arranged in rows, and bit positions are arranged in columns. For instance, word line **202** enables access to all of the bits in the memory word represented by that row, while word line **204** enables access to all of the bits in the succeeding memory word in the memory space provided by memory array **200**.

Each column in memory array **200** represents a bit position within a word. Thus, bit line  
20 **206** and its complement bit line **208** represent a particular bit position, while bit line **210** and its complement bit line **212** represent the succeeding bit position. Note that all of memory cells corresponding to a particular bit position are connected to the same word lines. Thus, each individual memory cell in memory array **200** is accessed by row and column.

In “system on a chip” (SoC) applications, where a complete system of components is  
25 manufactured on a single integrated circuit (IC), SRAM arrays, such as that depicted in **Figure 2**, may serve any of a variety of functions. The six-transistor SRAM cell depicted in **Figure 1** (memory circuit **100**) is regarded as being the most common SRAM cell currently in use in industry, since the six-transistor SRAM cell is fast and also suitable for high-density applications, where space in the IC layout is at a premium.

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Since memory cells are typically implemented in a two-dimensional array, such as that depicted in **Figure 2**, there will generally be some form of wire-length-related delay or latency between the time that a word line is strobed for a read operation and the time that the desired data appears on the bit lines at the periphery of the array (where the data can be latched or otherwise used). Self-timed memory circuits are often used to address this problem. In a typical self-timed memory circuit, a self-timed row decoder circuit is located at the top of the memory array so as to mimic the wire delay from the memory's control block (at the bottom of the array) up to the top row decoder of the memory. In the typical case, the self-timed row decoder circuit drives a signal that is allowed to propagate from the top of the array to the bottom of the array, where the sense amplifiers for the memory array are located. In this way, the maximum wire delay experienced by the data signals being read from the memory would be estimated, since the top row of memory cells would have the highest amount of wire delay from the perspective of the sense amplifiers at the bottom of the array.

In some applications programmability, or at least simplicity of the design process, becomes a priority. When rapid turnaround time or ease of manufacturing is needed, a "programmable" IC, which provides a standardized, generic set of components, such as logic gates or memory cells, can be "programmed" to implement the desired functionality. Thus, rather than laying out each individual transistor circuit in the design, a designer can simply make or break connections between the standard, generic components in the IC to achieve the desired result. Many devices that are called "programmable" may be programmed using some sort of programming apparatus, such as an FPGA (field-programmable gate array) programmer device. Another form of "programming" is "metal programming," in which one or more metal layers in the layout of an IC are used to form connections between standard components. "Metal programming" is useful for implementing IC designs that are to be commercially manufactured. In general, metal programming allows the designer the convenience of designing a circuit using a programmable device as a basis for the design, but "metal programming" is also rather conducive to mass manufacture, as the "programmed" part of the IC can simply be implemented as a layer in the usual fabrication process, rather than by having to "burn" the programmed part into the IC using a special programmer device.

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In the design of metal-programmable memories, the self-timed architecture can restrict the number of ways in which the memory can be broken up. **Figure 5** is an example of a memory array design that illustrates this problem. In **Figure 5** a contiguous 512-by-512 array of memory cells with 2 input/output (I/O) blocks **504** and **506** (i.e., with two sets of sense amplifiers and related read/write circuitry) at the top and the bottom is segmented horizontal boundary line at a location of choice between the top and bottom of the array so as to form two adjacent memory arrays **500** and **502**. Each of I/O blocks **504** and **506** operates only on its respective part of the original 512-by-512 memory array (i.e., on memory array **500** and memory array **502**, respectively). This requires that self-timing row decoders **508** and **510** be located at the boundary line separating row decoder regions **507** and **509**, which are the row decoders for memory array **500** and memory array **502**, respectively. If a design calls for dividing the memory cell array in many areas by only changing metal routing layers, then self-timed row decoders and associated dummy bit cells (for reading the self-timing signals) must be placed in numerous places. This requires that free layout space be reserved at all of the locations in which a possible breakpoint or boundary line in the memory array can be located. This can use up a tremendous amount of layout area if many different possible breakpoints are desired.

Thus, a need exists for a self-timed memory circuit that allows a memory array to be broken into multiple segments without reserving large portions of layout space within the array for self-timing circuitry.

### SUMMARY OF THE INVENTION

The present invention provides a novel design for a self-timed memory array in which segmentability and metal-programmability are supported while minimizing the amount of layout space required for implementing these functionalities. In a preferred embodiment, two self-timing row decoder circuits are utilized to support all possible array segmentations. The self-timing row decoder circuits are placed at the top and bottom of the array adjacent to respective I/O blocks. The self-timing signal is routed from the top (resp. bottom) of the array to a point halfway down (resp. up) the memory array and then back to a self-timing row decoder at the top (resp. bottom) of the array. This allows the wire delay for the activation of the real row decoders at the bottom (resp. top) of the memory array to be taken into account without having to place self-timing circuitry at both ends of the array. The same approach may also be used to account for the bitline wire delay from the bottom (resp. top) of the array to the sense amplifiers in the I/O block. In a preferred embodiment, dummy bitcells are placed at the top (resp. bottom) of the array close to the sense amplifiers, but the dummy bitcells will drive a bitline downward (resp. upward) to a point halfway across the array, from which the signal is routed back up (resp. down) to a dummy sense amplifier, so as to take into account the full bitline wire delay across the memory array.

In a preferred embodiment, memory arrays of various sizes may be implemented by way of metal programmability. By selectively including or eliminating metal routing layers from particular memory cells, additional routing area can be freed up for connecting other portions of a design. Further flexibility may be achieved by using a programmable gate array to implement circuitry for supporting a desired word size, so that a word size of choosing may be achieved from a memory array exhibiting minimum-column decoding.

### BRIEF DESCRIPTION OF THE DRAWINGS

The novel features believed characteristic of the invention are set forth in the appended  
5 claims. The invention itself however, as well as a preferred mode of use, further objects and  
advantages thereof, will best be understood by reference to the following detailed description of an  
illustrative embodiment when read in conjunction with the accompanying drawings, wherein:

**Figure 1** is a schematic diagram of a six-transistor single-port SRAM cell as known in  
the art;

10 **Figure 2** is a schematic diagram of a single-port SRAM array as known in the art;

**Figure 3** is a diagram of an integrated circuit layout for a six-transistor SRAM cell;

**Figure 4** is a diagram of an integrated circuit layout for a six-transistor SRAM cell that  
has been disabled through metal programming;

15 **Figure 5** is a diagram of a typical segmented memory array having self-timing circuitry as  
known in the art;

**Figure 6** is a diagram of a self-timed segmented memory array in accordance with a  
preferred embodiment of the present invention;

**Figure 7** is a diagram of circuitry for supporting a desired word size in a memory array  
made in accordance with a preferred embodiment of the present invention;

20 **Figure 8** is a diagram of a programmable integrated circuit for providing memory having  
a desired word size in accordance with a preferred embodiment of the present invention; and

**Figure 9** is a flow diagram of a process of designing an integrated circuit in accordance  
with a preferred embodiment of the present invention.



### DETAILED DESCRIPTION

**Figure 6** is a diagram of a self-timed memory array design in accordance with a preferred embodiment of the present invention. Memory array **600** and memory array **602** are separate memory arrays formed by dividing a base design for a larger memory array into two segments as in **Figure 5**. Unlike the memory design of **Figure 5**, however, this preferred embodiment of the present invention is designed with the self-timing circuitry for each memory array residing on a single side of the array. With respect to memory array **600**, for example, a self-timing row decoder **610** resides on the same side of the memory array **600** as I/O block **604** (i.e., the “top” of memory array **600**, as depicted in **Figure 6**). A metal routing path **620** extends midway into row decoder region **607** of memory array **600** such that the wire delay experienced along routing path **620** is approximately the same as would be experienced along a wiring path extending from a row decoder at the bottom of row decoder region **607** to the top of row decoder region **607**. Thus, self-timing row decoder **610**, by receiving a self-timing signal that travels along routing path **620** into row decoder region **607** of memory array **600** and back again, simulates the effect of having a self-timing row decoder at the boundary between row decoder region **607** and row decoder region **609** so that extra layout space for row-decoding circuitry at that boundary need not be allocated in the design. Similarly, self-time row decoder **608** receives a self-timing signal along routing path **622** that extends into row decoder region **609** of memory array **602** and back, so as to simulate the effect of placing self-timing circuitry at the boundary between memory array **600** and memory array **602**.

A similar self-timing apparatus may be employed for approximating the wire delay experienced on a bit line in a memory array. With respect to memory array **602**, for example, dummy bit cell **618** emits a signal that travels along routing path **624**. Routing path **624** extends about midway into memory **602** before returning to dummy sense amplifier **616** in I/O block **606**. The round-trip wire delay approximates the delay that would be experienced along a bit line from a memory cell (bit cell) residing at the upper edge of memory array **602** down to a sense amplifier in I/O block **606**, but without requiring additional circuitry between memory arrays **600** and **602**.

An additional advantage to this self-timing memory design is that it allows unused portions of a memory array to be freed up for metal routing. For example, suppose that a given ASIC

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(application-specific integrated circuit) design does not require the fully memory capacity of an available memory array. With respect to **Figure 6**, one could suppose that only memory **602** was needed for the particular application. Since the self-timing circuitry all resides on the bottom half of memory array **602** (rather than the typical case of extending from the top of memory array **600** down to the bottom of memory array **602**, if one considers memory arrays **600** and **602** to form one larger memory array), memory array **600** (the unused portion of the larger memory array) can be used for routing other signals without interference from self-timing signals.

More specifically, if we turn our attention to **Figure 3**, which is a layout diagram of a typical SRAM cell, we notice that an SRAM cell (like any integrated circuit) is made up of many regions of overlapping layers of different materials. Power supply rails **300** and **306** and bit lines **302** and **304** are layers of metal, while other portions of the SRAM cell are manufactured from positively and negatively doped silicon (e.g., P-diffusion region **314** and N-diffusion regions **312**) or oxide (e.g., polysilicon region **310**, which forms a word line). Different material layers are connected by way of contacts (e.g., contact **316**), which may be ohmic contacts, vias, or other forms of contacts. In a preferred embodiment of the present invention, an SRAM cell residing in an unused portion of a memory array can be reclaimed for routing metal routing paths by eliminating the metal regions and contacts in the SRAM cell through metal programming, as shown in **Figure 4**. Once the connectors that would connect the transistors of the SRAM cell to metal lines are eliminated, a designer is free to route metal lines over the unused SRAM cell as desired. Since in a preferred embodiment of the present invention, no metal routing paths are needed to support self-timing in unused memory array segments, routing paths in these unused memory segments are available without interference from routing paths needed for self-timing operation.

Further design flexibility may be afforded by allowing a designer to select a desired word size for use in addressing the memory array. **Figure 7** demonstrates how this may be accomplished. **Figure 7** shows a memory array **700** in accordance with a preferred embodiment of the present invention. Memory array **700** is designed for minimum-column decode. That is to say, memory array **700** presents output from all of its bit lines when a given word line is addressed (i.e., memory array **700** outputs the minimum number of columns, namely one). In the example provided in **Figure 7**, memory array **700** has 80 bit lines. A multiplexer **702** is coupled to memory

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array **700** such that the address presented to multiplexer **702** at selection input **706** selects one of four 20-bit words that can be derived from the 80-bit single memory column. In a preferred embodiment, multiplexer **702** is constructed using programmable logic. **Figure 8** shows a programmable gate array **800** having a multi-line connection **804** to a self-timed memory array **802**.

5 Since programmable gate array **800** can be programmed to implement a multiplexer having any number of possible inputs, one skilled in the art could program gate array **800** to implement a multiplexer having the correct number of multiple-bit inputs to obtain a desired word size. Thus while **Figure 7** depicts a design that provides for a 20-bit word size, one skilled in the art could utilize a differently-programmed multiplexer with the same memory array to obtain a different word  
10 size, such as 40 bits, for example.

A design process used to produce metal-programmable memories in accordance with a preferred embodiment of the present invention is depicted in the form of a flow diagram in **Figure 9**. A circuit designer may use a computer-based text editor program **900** or some other form of editing facility (whether graphical or text based) to input characteristics of a design to be  
15 implemented. Typically, this is performed using some form of hardware definition language, such as Verilog. These design characteristics will form a relatively high level description **902** of the memory system that can be fed into a compiler program **904** as input. Compiler **904** translates description **902** into a layout **906** by varying the metal layer(s) of a standard circuit layout so as to achieve a layout implementing an electrical circuit that functions according to the  
20 designer's requirements. Layout **906** can then be used to direct a fabrication process **908**, as is known in the art. Since only the metal layer portion of the design is varied by the metal-programming process, when the circuit is fabricated, only those semiconductor masks that affect the metal-layer layout need be customized for the given design, and standardized masks can be used for the other circuit layers.

25 It is important to note that while the present invention has been described in the context of a fully functioning data processing system, those of ordinary skill in the art will appreciate that the processes of the present invention are capable of being distributed in the form of a computer readable medium of instructions or other functional descriptive material and in a variety of other forms and that the present invention is equally applicable regardless of the particular type of

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signal bearing media actually used to carry out the distribution. Examples of computer readable media include recordable-type media, such as a floppy disk, a hard disk drive, a RAM, CD-ROMs, DVD-ROMs, and transmission-type media, such as digital and analog communications links, wired or wireless communications links using transmission forms, such as, for example,  
5 radio frequency and light wave transmissions. The computer readable media may take the form of coded formats that are decoded for actual use in a particular data processing system.

Functional descriptive material is information that imparts functionality to a machine.

Functional descriptive material includes, but is not limited to, computer programs, instructions, rules, facts, definitions of computable functions, objects, and data structures.

10 The description of the present invention has been presented for purposes of illustration and description, and is not intended to be exhaustive or limited to the invention in the form disclosed. Many modifications and variations will be apparent to those of ordinary skill in the art.

The embodiment was chosen and described in order to best explain the principles of the invention, the practical application, and to enable others of ordinary skill in the art to understand  
15 the invention for various embodiments with various modifications as are suited to the particular use contemplated.